

| L Number | Hits  | Search Text   | DB                               | Time stamp       |
|----------|-------|---|----------------------------------|------------------|
| 1        | 27606 | ((low near10 dielectric) (organo near3 silic\$5 near3 glass))   | USPAT;<br>US-PGPUB               | 2003/04/02 15:57 |
| 2        | 1300  | ((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))   | USPAT;<br>US-PGPUB               | 2003/04/02 15:51 |
| 3        | 2539  | ((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))  | USPAT;<br>US-PGPUB               | 2003/04/02 15:52 |
| 4        | 3454  | ((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma)))   | USPAT;<br>US-PGPUB               | 2003/04/02 15:20 |
| 5        | 2106  | ((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))  | USPAT;<br>US-PGPUB               | 2003/04/02 15:58 |
| 6        | 1848  | ((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))) and (via trench hole open\$4)   | USPAT;<br>US-PGPUB               | 2003/04/02 15:23 |
| 7        | 361   | ((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))) and (via trench hole open\$4)) and (wet near8 (treat\$3 etch\$3 clean\$3))  | USPAT;<br>US-PGPUB               | 2003/04/02 15:53 |
| 8        | 206   | ((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))) and (via trench hole open\$4)) and (wet near8 (treat\$3 etch\$3 clean\$3))) and (HF (hydrogen near3 fluoride) (hydro near3 fluoric near3 acid) (sulfuric near3 acid) ("H.sub.2" adj "SO.sub.4") ((citric acetic oxallic) near5 acid)) | USPAT;<br>US-PGPUB               | 2003/04/02 15:55 |
| 9        | 17236 | ((low near10 dielectric) (organo near3 silic\$5 near3 glass))   | EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/04/02 15:51 |
| 10       | 123   | ((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))   | EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/04/02 15:52 |
| 11       | 123   | ((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))  | EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/04/02 15:52 |
| 12       | 235   | ((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma)))   | EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/04/02 15:52 |
| 13       | 34    | ((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))  | EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/04/02 15:52 |

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|----|------|---|----------------------------------|------------------|
| 14 | 2    | (((((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))) and (wet near8 (treat\$3 etch\$3 clean\$3))  | EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/04/02 15:53 |
| 15 | 2    | (((((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (plasma near10 (treat\$6))) (((low near10 dielectric) (organo near3 silic\$5 near3 glass))) and (reduc\$3 near5 (agent gas plasma))) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))) and (HF (hydrogen near3 fluoride) (hydro near3 fluoric near3 acid) (sulfuric near3 acid) ("H.sub.2" adj "SO.sub4") ((citric acetic oxallic) near5 acid)) | EPO; JPO;<br>DERWENT;<br>IBM_TDB | 2003/04/02 15:58 |
| 16 | 4772 | (damascene (dual near3 damascene))  | USPAT;<br>US-PGPUB               | 2003/04/02 15:57 |
| 17 | 779  | ((damascene (dual near3 damascene))) and (((low near10 dielectric) (organo near3 silic\$5 near3 glass)) same plasma)  | USPAT;<br>US-PGPUB               | 2003/04/02 15:58 |
| 18 | 543  | ((damascene (dual near3 damascene))) and (((low near10 dielectric) (organo near3 silic\$5 near3 glass)) same plasma)) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))  | USPAT;<br>US-PGPUB               | 2003/04/02 15:58 |
| 19 | 162  | ((damascene (dual near3 damascene))) and (((low near10 dielectric) (organo near3 silic\$5 near3 glass)) same plasma)) and (hydrogen "H.sub.2" and (argon Ar nitrogen "N.sub.2"))) and (HF (hydrogen near3 fluoride) (hydro near3 fluoric near3 acid) (sulfuric near3 acid) ("H.sub.2" adj "SO.sub4") ((citric acetic oxallic) near5 acid))  | USPAT;<br>US-PGPUB               | 2003/04/02 15:59 |